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TECHNOLOGY CENTER 2800

Form PTO-1449 (Modified)										Atty Docket No.: G0244	Serial No.: 10/050,456
LIST OF PATENTS AND PUBLICATIONS O I P FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary) MAR 21 2002										Applicant: Khoi A. Phan, et al.	
										Filing Date: 1/16/02	Group: 2812

REFERENCE DESIGNATION

U.S. PATENT DOCUMENTS

Examiner Initial		Document Number									Date	Name	Class	Subclass	Filing Date if Appropriate
22	A	4	7	1	9	7	0	5	01/19/98	Laganza, et al.	—	—	—	—	
22	B	4	7	6	0	4	2	9	07/26/88	O'Connor	—	—	—	—	
22	C	4	7	6	8	8	8	3	09/6/88	Waldo, et al.	—	—	—	—	
22	D	4	8	2	4	4	9	6	04/25/89	Seifert, et al.	—	—	—	—	
22	E	4	9	2	2	8	2	2	05/08/90	Bierschenk et al.	—	—	—	—	
22	F	5	0	6	4	4	7	6	11/12/91	Recine, Sr.	—	—	—	—	
22	G	5	1	7	1	3	7	2	12/15/92	Recine, Sr.	—	—	—	—	
22	H	5	5	2	2	2	2	5	06/04/96	Eskandari	—	—	—	—	
22	I	5	6	0	4	7	5	8	02/18/97	AuYeung et al.	—	—	—	—	
22	J	5	6	8	9	9	5	7	11/25/97	DeVilbiss, et al.	—	—	—	—	
22	K	5	6	8	9	9	5	8	11/25/97	Gaddis, et al.	—	—	—	—	
22	L	5	6	9	0	8	4	9	11/25/97	DeVilbiss, et al.	—	—	—	—	
22	M	5	7	0	4	2	1	3	01/06/98	Smith et al.	—	—	—	—	
22	N	5	7	2	7	6	8	5	03/17/98	Laganza et al.	—	—	—	—	
22	O	5	7	8	0	8	6	1	07/14/98	Apelgren et al.	—	—	—	—	
22	P	5	8	2	2	9	9	3	10/20/98	Attey	—	—	—	—	
22	Q	5	8	6	7	9	9	0	02/9/99	Ghoshal	—	—	—	—	
22	R	5	9	4	0	7	8	4	08/17/99	El-Husayni	—	—	—	—	
22	S	6	0	9	8	4	0	8	08/8/00	Levinson, et al.	—	—	—	—	

OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)

22	T		EUV Lithography (First of Two Parts), Andrew M. Hawryluk et al., SOLID STATE TECHNOLOGY, July 1997, pp 151, 152, 154, 156, and 159.
22	U		EUV Lithography (Second of Two Parts), Andrew M. Hawryluk et al., SOLID STATE TECHNOLOGY, August 1997, pp 75, 76, and 78.

EXAMINER	<i>R. S. Full</i>	DATE CONSIDERED
		11-25-02

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.